AIMCAL R2R Conference 2017 plasma polymer thin films fabricated by large area roll-to-roll sputtering process

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Introduction

- Preparation
- ***** Results





Surface Functional Thin Film Coating

<u>Camera Lens用 Coating</u>



Display用 Coating



AR Coating

AF Coating



<u>Low – E</u>



Flexible Hard Coatings for OLED Lighting





Vitex Barrier film



Gorilla + Anti-bacteria







Conventional Polymer Coating Process

Wet Coating Process







Evaporation Process





CVD Process













Sputtering Process (Radio Frequency)





Previous Reports

- **R. Harrop & P. J. Harrop**, FRICTION OF SPUTTERED PTFE FILMS, Thin Solid Films, 3 (1969) 109-117 : First report on the RF-Sputtered PTFE thin film
- D.T. Morrison & T. Robertson, RF Sputtering of Plastics, Thin Solid Films, 15 (1973) 87-101
 - : RF sputtering of PTFE to obtain insulating layer for capacitor

Hydek Biederman Group (Czech, Charles University)

- : Studied plasma polymer thin film using various polymer targets such as PTFE, PE, PI, etc by RF sputtering process
- : Reported Superhydrophobic, Optical properties, multilayer, co-sputtering layer, etc. for over 40 years







Previous Reports

- S. Iwamori Group (Japan, Kanazawa University)
- : Reported RF-Sputtered plasma polymer fluorocarbon thin films focused on the adhesion and tribological properties



F. Faupel Group (Germany, Kiel University)

: Reported Co-Sputtered organic/metal composite fluorocarbon thin films using two RF sputtering cathodes



Nanotechnology 16 (2005) 1078-1082



Thin Solid Films 515 (2006) 801-804



Journal of Physics: Conference Series 100 (2008) 052043







Large Area Deposition by pilot scale Roll-to-Roll Sputtering

- Composite Target : CNT 5 wt% / PTFE 95 wt%
- Target Size : 127 mm × 950 mm × 6mm
- Roll (Line) Speed : 1 m/min
- MF power : 3 kW
- Base/Working Pressure : 5×10^{-5} Pa / 4.85×10^{-1} Pa
- Pre-treatment : Heat treatment@300°C, Ar/O₂ Plasma Treatment
- Coating Length : > 100 m





Transmittance ~ 92%





Film Thickness ~ 100 nm Water Contact Angle ~ 115°







Multi-functional hydrophobic coating

R2R Sputter Process









MF & DC Sputtering Process













D1 = 111.80 nm

Fluorocarbon Nano-Thin Film Properties

High transparency





500 nm

Hydrophobic & Oleophobic



SiO2

Nano-Coating on SiO2

Amorphous structure



Surface Hardness













Multi-functional hydrophobic coating

Bending Test

0

Twisting Test

(11 · (0 44 (0 11 0) 40 Etec 1MD1 15 KHU 17





Surface Hardness ~ 1.4 GPa

Rolling Test

Surface Hardness ~ 6.9 GPa







Substrate : Glass, Film, Fabric, Metal, Paper etc



nemical Technology



Various Applications of Sputtered Fluorocarbon Thin Films









Plasma Polymer Fluorocarbon Thin Films

- CNT/PTFE composite targets show enough conductivities to generate plasma in Mid-Range Sputtering Process
- Sputtered fluorocarbon thin films exhibit high optical transparency, hydrophobicity, surface hardness simultaneously
- Sputtered fluorocarbon thin film shows excellent mechanical flexibility because of amorphous structure.
- Possible to make Flexible-High Hardness, Hydrophobic, Transparent Nano-Thin Film for flexible/rollable/foldable display devices.
- We succesfully demonstrate large area fluorocarbon thin film using pilot scale roll-to-roll sputtering equipment.







Thank you!!



